

PATENT

Atty. Dkt. No. AMAT/2801.P11/PPC/ECP/RKK

REMARKS

This is intended as a full and complete response to the Final Office Action dated August 18, 2004, having a shortened statutory period for response set to expire on November 18, 2004. Please reconsider the claims pending in the application for reasons discussed below.

Claims 1 - 8, 10, 12, 13 and 23 remain pending in the application and are shown above. Claims 24 - 37 have been cancelled by the Applicant and claims 1 - 8, 10, 12, 13 and 23 are rejected by the Examiner. Reconsideration of the rejected claims is requested for reasons presented below.

Claims 1, 3 and 7 are amended to clarify the invention. Independent claims 1 and 3 as amended incorporate a feature from dependent claim 7. Therefore, the amendments do not present a new issue.

Claims 1 - 8, 10, 12, 13 and 23 stand rejected under 35 U.S.C. §103(a) as being unpatentable over *Hey, et al.*, U.S. Patent No. 6,551,488 in view of *Rattan, et al.*, U.S. Patent No. 4,489,740. Applicant respectfully traverses the rejection. The references do not teach or provide motivation for an integrated bevel cleaning (IBC) apparatus, having a transfer position where a substrate is positioned, a rinse position where the substrate is rinsed, an etch position where the edge of the substrate is cleaned, a linear actuator for positioning the substrate in the transfer position, the rinse position and the etch position, and a plurality of cooperatively movable etchant dispense nozzles coupled to at least one etchant dispensing arm assembly positioned proximate the etch position and rotatably positionable near and away from the substrate, the arm and nozzles being cooperatively configured to dispense an etchant onto the front side and backside of the substrate, as recited by claim 1. Withdrawal of the rejection to claim 1, and claims dependent thereon, is respectfully requested.

Further, Applicant submits that the references, in combination, do not teach or provide motivation for an integrated bevel cleaning (IBC) apparatus, having a transfer position where a substrate is positioned, a rinse position where the substrate is rinsed, an etch position where the edge of the substrate is cleaned, a linear actuator for positioning the substrate in the transfer position, the rinse position and the etch position,

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a plurality of cooperatively movable etchant dispense nozzles configured to dispense an etchant onto the front side and backside of the substrate, a substrate centering hoop for supporting the substrate in the transfer position, and a substrate centering hoop rinsing nozzle, as recited in claim 3. Withdrawal of the rejection to claim 3, is respectfully requested.

In conclusion, the references cited by the Examiner, in combination, do not teach, show, or suggest the invention as claimed.

Having addressed all issues set out in the Final Office Action, Applicant respectfully submits that the claims are in condition for allowance and respectfully request that the claims be allowed.

Respectfully submitted,



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